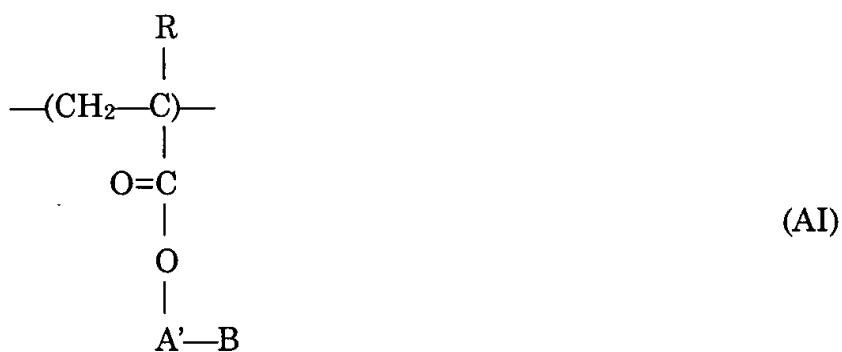
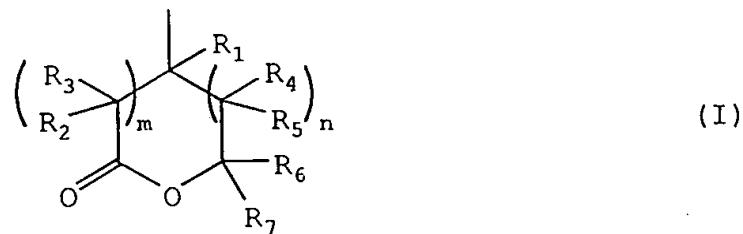


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(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit represented by the following formula (AI):



wherein R represents hydrogen atom, a halogen atom, a substituted or unsubstituted alkyl group having from 1 to 4 carbon atoms, A' represents a single bond and B represents a group represented by formula (I):



wherein R<sub>1</sub> represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R<sub>2</sub> to R<sub>7</sub>, which may be the same or different, each represents hydrogen atom, an alkyl group which may have a substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R<sub>6</sub> and R<sub>7</sub> is not a hydrogen atom and R<sub>6</sub>

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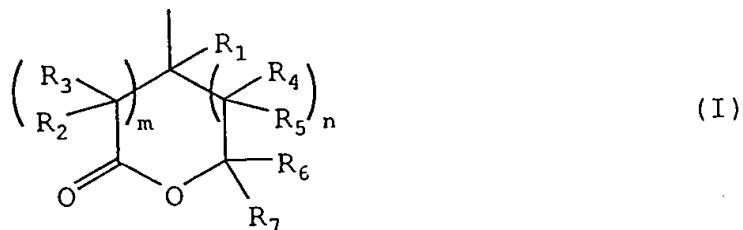
and R<sub>7</sub> may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.

9 (Amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid upon irradiation with actinic rays or radiation,

(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit having a group represented by the following formula (I), and

(C) a fluorine-containing and/or silicon-containing surfactant:



wherein R<sub>1</sub> represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R<sub>2</sub> to R<sub>7</sub>, which may be the same or different, each represents hydrogen atom, an alkyl group which may have a substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R<sub>6</sub> to R<sub>7</sub> is not a hydrogen atom and R<sub>6</sub>

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*a<sup>2</sup>* and R<sub>7</sub> may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.

*a<sup>3</sup>* 18 (Amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid upon irradiation with actinic rays or radiation,

(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit represented by the following formula (AI), and

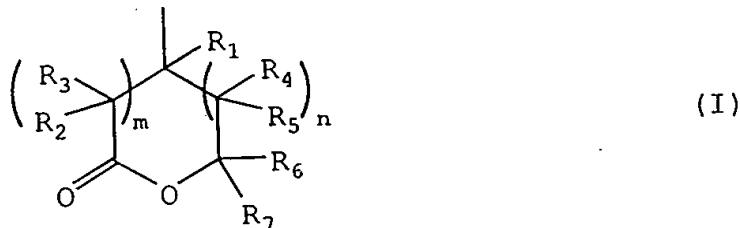
(D) a solvent containing the following solvent (a) in an amount of 60% to 90 wt % based on the entire solvent:

(a) at least one first solvent selected from propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether propionate, methyl 3-methoxypropionate, ethyl 3-methoxypropionate, methyl 3-ethoxypropionate and ethyl 3-ethoxypropionate;



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wherein R represents hydrogen atom, a halogen atom, a substituted or unsubstituted alkyl group having from 1 to 4 carbon atoms, A' represents a single bond and B represents a group represented by formula (I):



wherein R<sub>1</sub> represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R<sub>2</sub> to R<sub>7</sub>, which may be the same or different, each represents hydrogen atom, an alkyl group which may be substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R<sub>6</sub> and R<sub>7</sub> is not a hydrogen atom and R<sub>6</sub> and R<sub>7</sub> may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.